

ITO

INDIUM TIN OXIDE

Application

Indium Tin Oxide ist used for the production of transparent, electrically conductive thin films.

Composition in wt%

In₂O₃ 90 ± 0.5
SnO₂ 10 ± 0.5

Forms of Delivery

The material is available in form of sputtering targets for PVD.
Bonding of the material onto a backing plate is strongly recommended.

Typical Analysis in wt%

ITO	99.99%
Cr	<0.0003
Cu	<0.0005
Fe	<0.0007
Ni	<0.0005

Physical properties

Melting point: ~ 1910 °C
Theoretical density: 7.11 g/cm³

